

Amendments To The Drawings:

None

Remarks

This Amendment is in response to the Office Action dated **June 12, 2007**. Claims 10 and 24-27 have been canceled.

Claims 1, 11 and 28 have been amended to include the feature that the alkaline compound is ammonia. That is, the polishing composition defined in these claims, as amended, includes colloidal silica having specific average primary and secondary particle sizes, ammonia, a water-soluble polymer, and water.

Claims 1-5, 7-10 and 18-28 §103(a) Tanaka v/ Inoue

Claims 1-5, 7-10 and 18-28 were rejected as being obvious over the combination of Tanaka et al, JP 2001-118,815 (Tanaka) in view of Inoue et al., U.S. Patent Publication 2001/0003672 (Inoue).

Tanaka discloses in paragraph 0015 that ammonia may be used as a strong base. However, as described in this paragraph of Tanaka, ammonia is necessarily used in combination with a **weak acid** in the polishing composition of Tanaka. Therefore, the polishing composition of Tanaka includes an ammonium salt, which will be partly dissociated into ammonium ion in the polishing composition, but does not include ammonia. Nothing in Tanaka or Inoue provides any basis for one of ordinary skill in the art to believe that a weak acid could be omitted. Thus, there is no basis for rejecting the amended claims since no combination fairly suggests use of ammonia as a strong base without also requiring a weak acid. The rejection is respectfully traversed.

Claim 19 has been amended to limit the colloidal silica content to 0.1 to 1 wt%. This amendment is supported by Examples 2-4 illustrated in the specification. Tanaka discloses in paragraph 0012 that the silicon oxide content is preferably 2 to 30 wt% but does not disclose or suggest the feature of claim 19, as amended. Neither reference provides any basis for having such

a low colloidal silica content. There is no reason one of ordinary skill in the art would lower the colloidal silica content in addition to using ammonia as a strong base without employing a weak acid. The rejection is respectfully traversed.

Conclusion

It is respectfully submitted that claims 1-5, 7-9, and 18-23, as amended, are patentable over the cited references. An early notice to that effect is requested.

Respectfully submitted,

VIDAS, ARRETT & STEINKRAUS

Date: September 11, 2007

By: /Scott Q. Vidas/
Scott Q. Vidas
Registration No.: 30812

6640 Shady Oak Dr., Suite 400
Eden Prairie, MN 55344-7834
Telephone: (952) 563-3000
Facsimile: (952) 563-3001

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